

Attorney Docket No.: 0180151

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

JAN 22 2008

In re Application of: Labelle, et al.

Serial No.: 10/705,347

Filed: 11/08/2003

For: Method for Integrating a High-K Gate  
Dielectric in a Transistor Fabrication  
Process

Art Unit: 1792

Examiner: Chen, Kin Chan

RESPONSE TO FINAL OFFICE ACTION

Reconsideration only.

kcc 1/15/08

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir/Madam:

This is in response to the *Final Office Action* dated November 19, 2007 in the above-referenced patent application. Please enter and consider the following remarks.